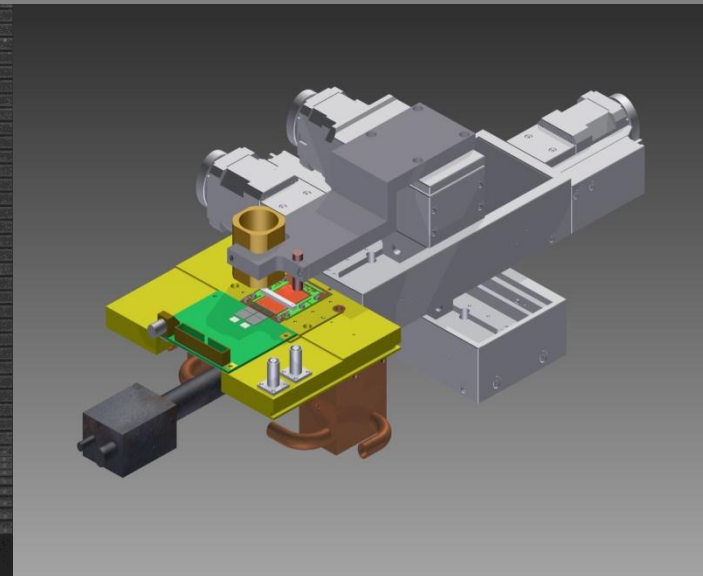
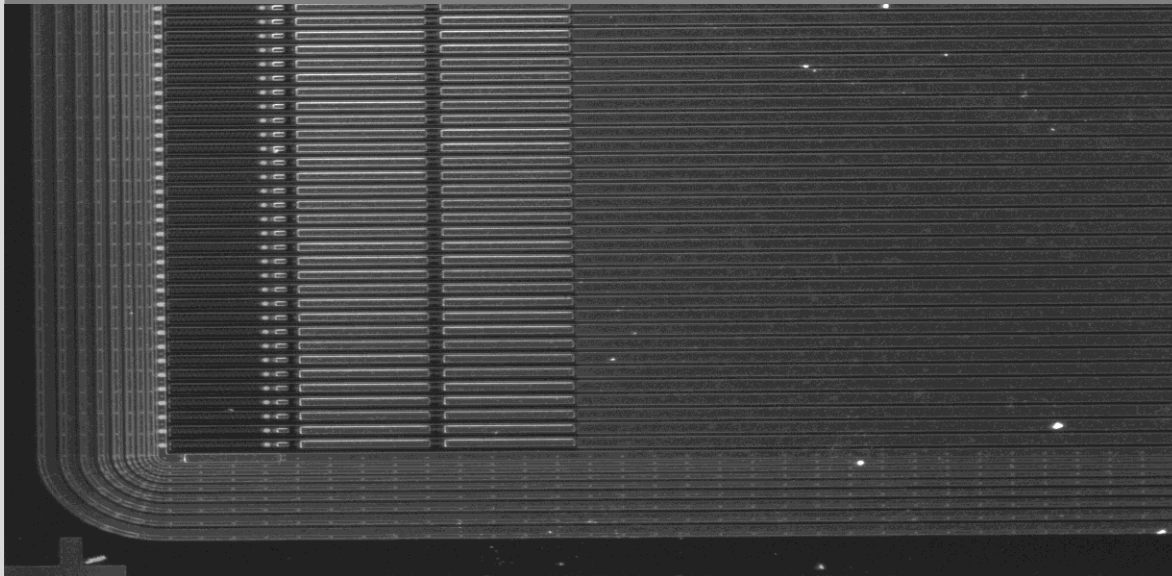


Different Charge Multiplication after proton and neutron irradiation

21st RD50 Workshop 14.11.- 16.11.2012

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Overview

- **Introduction**
 - **Overview of sensor properties**

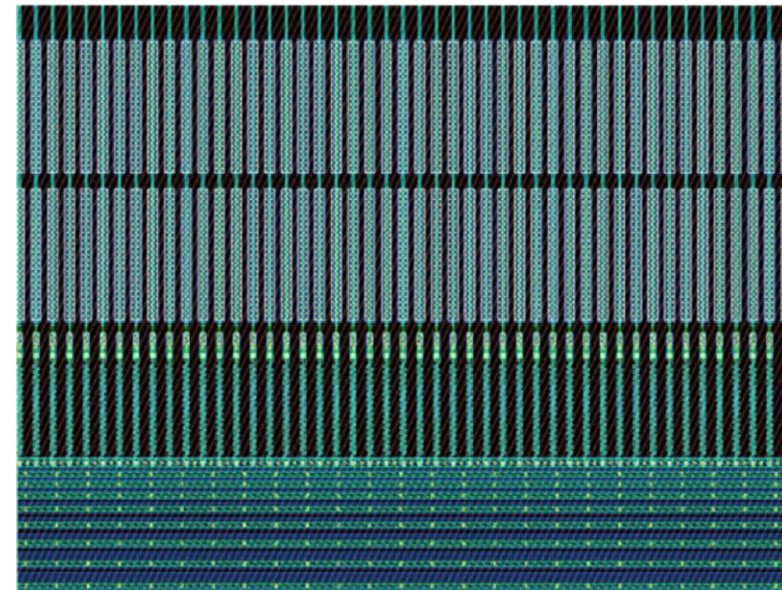
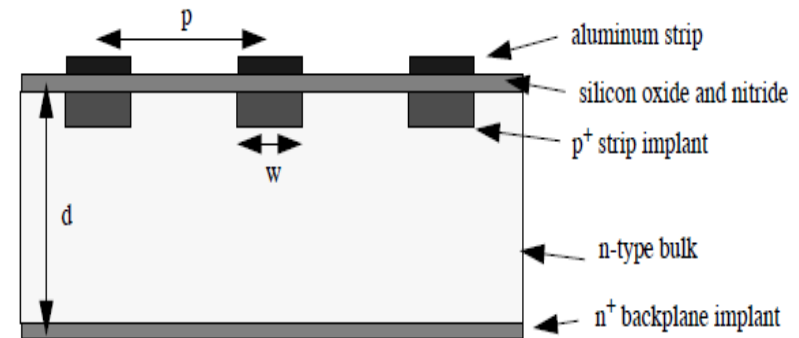
- **Comparison between neutron and proton irradiation**
 - **CCE**
 - **Signal to noise ratio**
 - **Leakage current**

- **Comparison between sensors with standard processing and sensors with double implant energy**

- **Summary**

RD50 CM-Sensors: Properties

- P-type sensors
 - 2 geometries
 - Depth $d = 305 \mu\text{m}$
 - Pitch $p = 80 \mu\text{m}$, **width $w = 6 \mu\text{m}$**
 - Pitch $p = 80 \mu\text{m}$, **width $w = 60 \mu\text{m}$**
 - Width/pitch $w/p = 0.075$ and $w/p = 0.75$
 - Active area: $10.18 \text{ mm} \times 11.76 \text{ mm}$
-
- 2 processings
 - **150keV** implantation energy
 - **300keV** implantation energy
 - 2 irradiations
 - Irradiation with **protons** in Karlsruhe
 - Irradiation with **neutrons** in Ljubljana
 - Same fluence $5 \cdot 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$

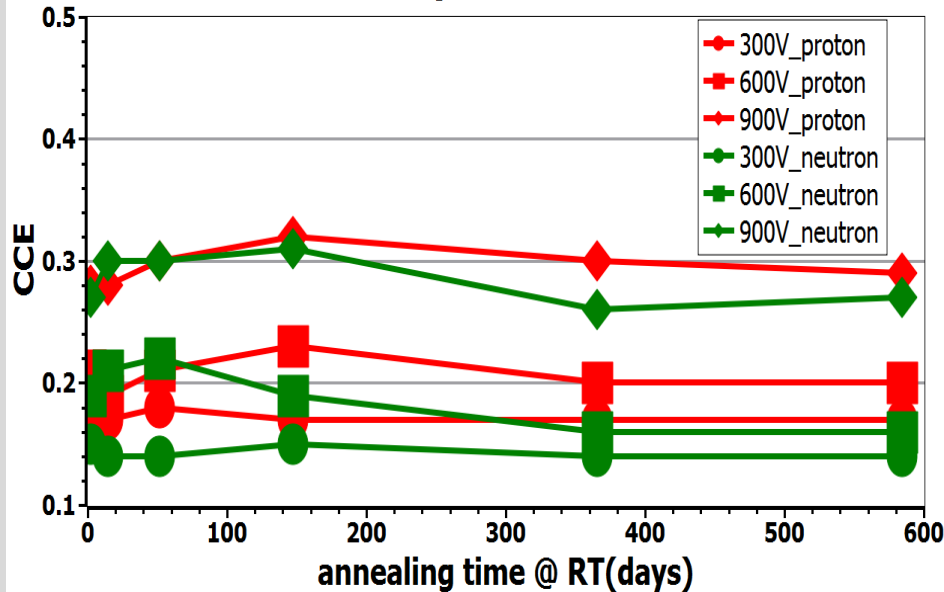


Measurement Results

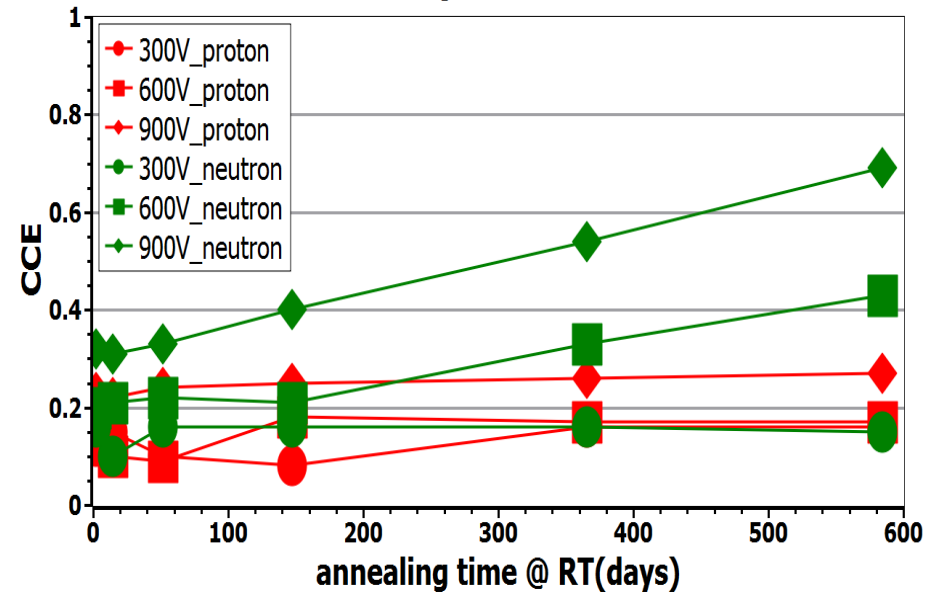
different width/pitch - ratio

Comparison between proton and neutron irradiation (CCE)

p80-w60



p80-w6



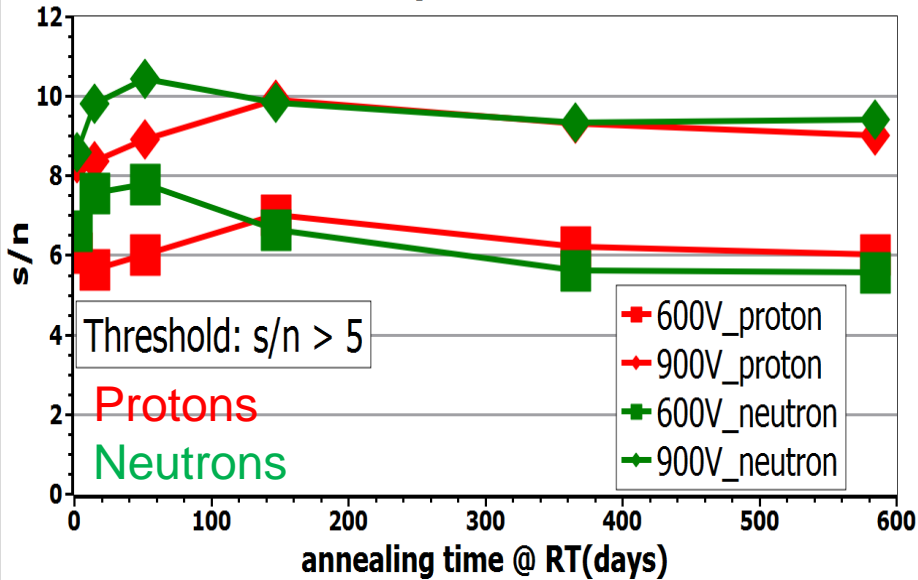
Broad implants show **usual** annealing behaviour

- Beneficial annealing up to 150d
- Reverse annealing later

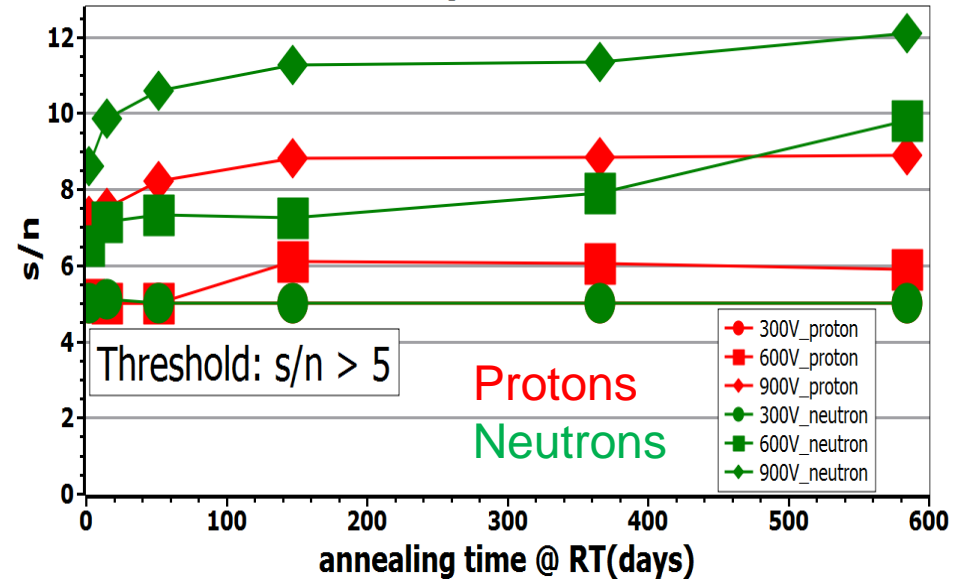
Narrow implants show **difference** between protons and neutrons: more CCE after neutron irradiation
Charge multiplication?

Signal to Noise (s/n)

p80-w60



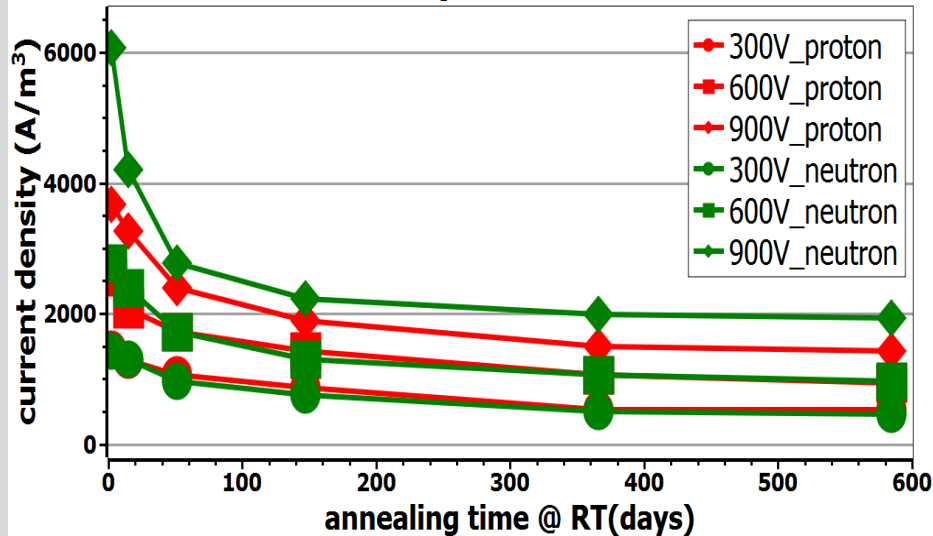
p80-w6



- s/n for proton irradiation independent of width
- s/n for neutron irradiation 25% larger for narrow strips

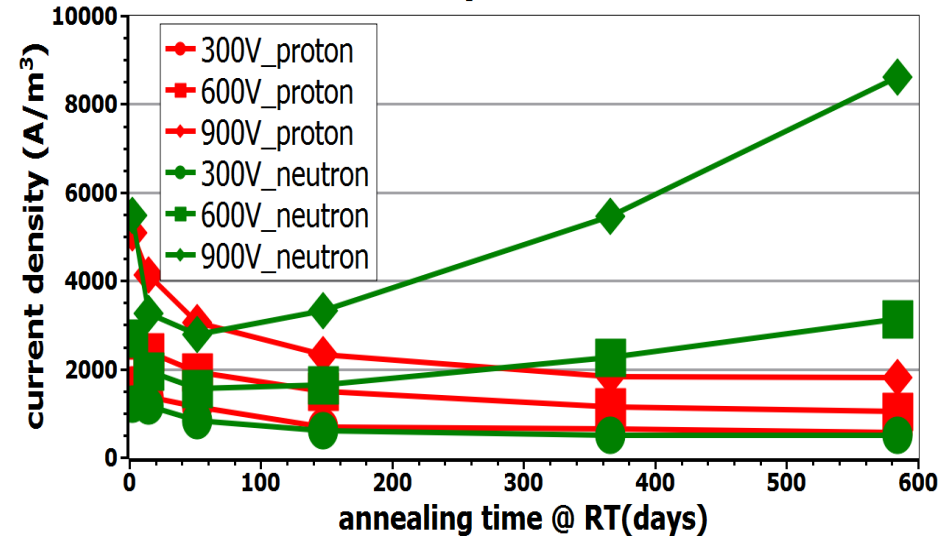
Leakage current

p80-w60



■ Decrease of current after annealing, both for neutrons and protons

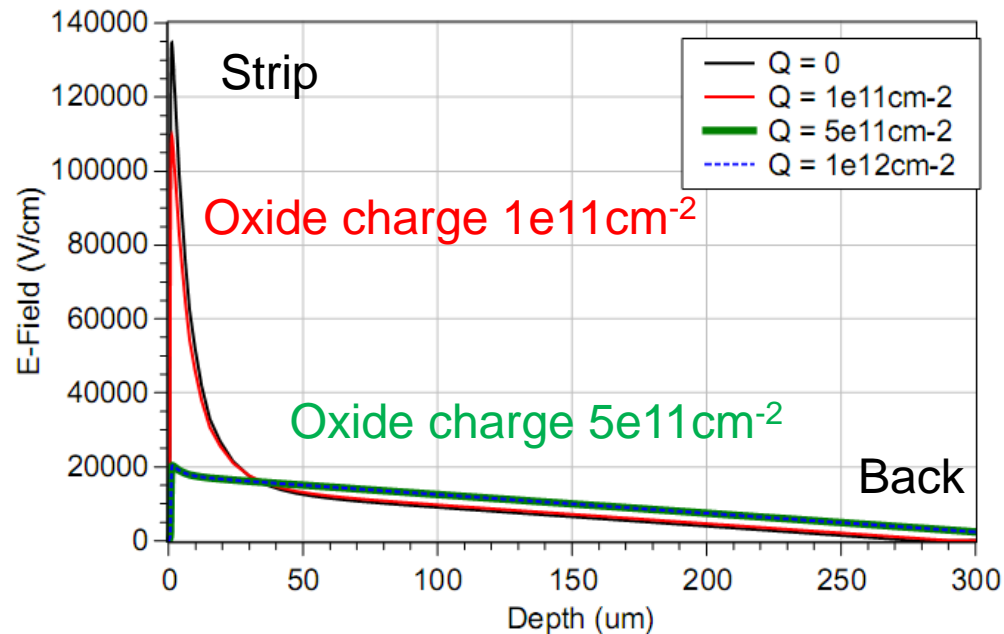
p80-w6



■ Increase of current after annealing for neutron irradiation

Possible explanation for difference between protons and neutrons

- Proton irradiation generates positive charge in the oxide / interface between silicon and oxide
- Neutron irradiation doesn't create much oxide / interface charge
- Preliminary simulation with interface charge shows:
 - Electric field decreases at the strip with increasing interface charge



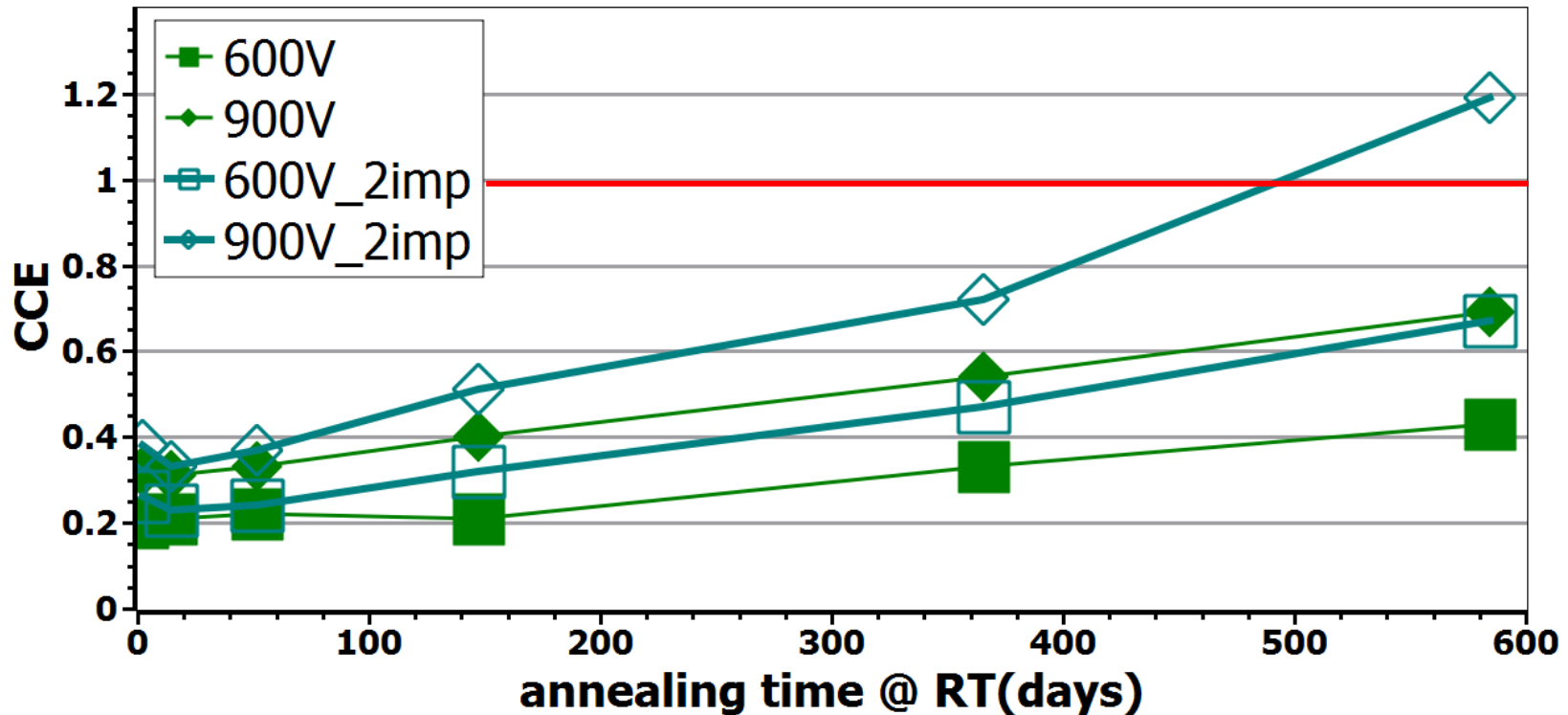
Different processings

Comparison between 150keV and 300keV implantation energy

Neutron irradiation to $F = 5 \cdot 10^{15} n_{eq}/cm^2$

Comparison of implantation energy (CCE)

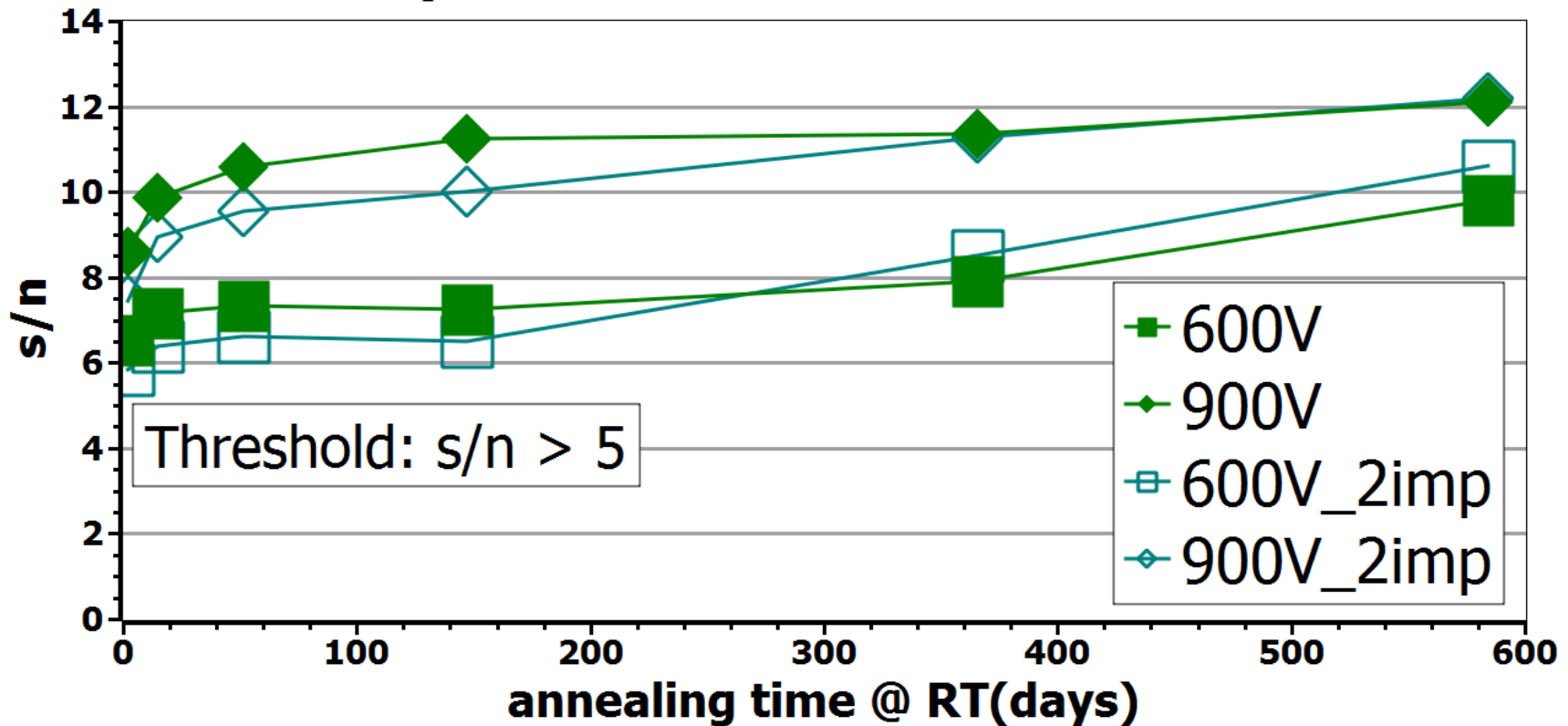
p80-w6: neutron irradiation



■ Doubling implantation energy almost doubles CCE
Charge Multiplication

Comparison of implantation energy (s/n)

p80-w6: neutron irradiation



■ Implantation energy does not influence s/n

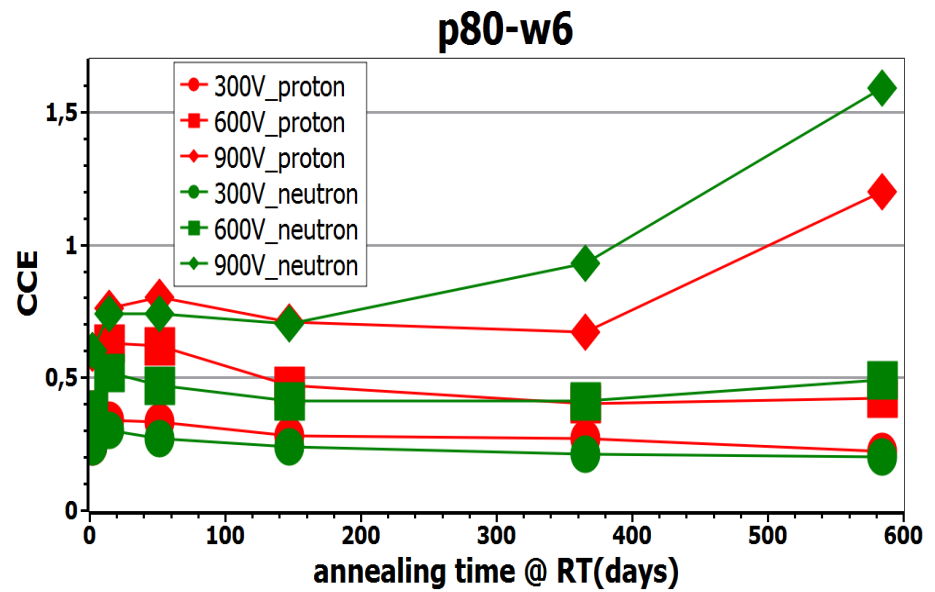
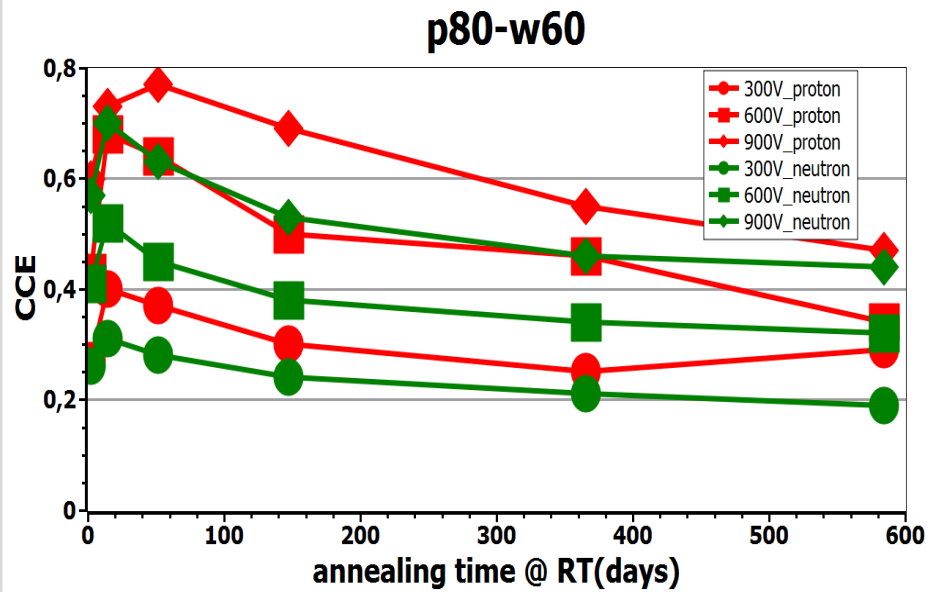
Summary

- **Only narrow implants show charge multiplication after neutron irradiation**
- **No charge multiplication after proton irradiation**
- **Possible explanation: more space charge in oxide after proton irradiation reduces electric field**
- **Larger implantation energy increases charge multiplication**

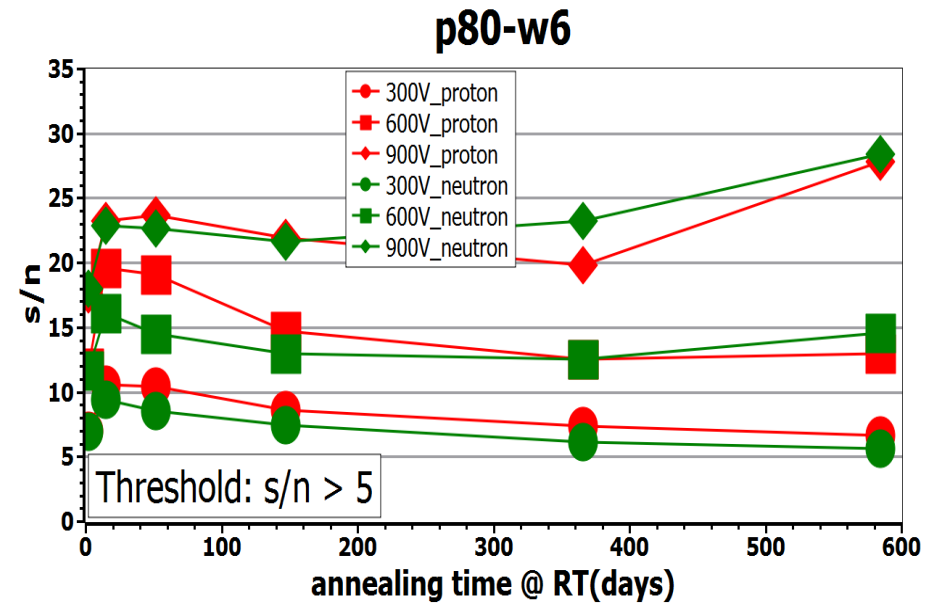
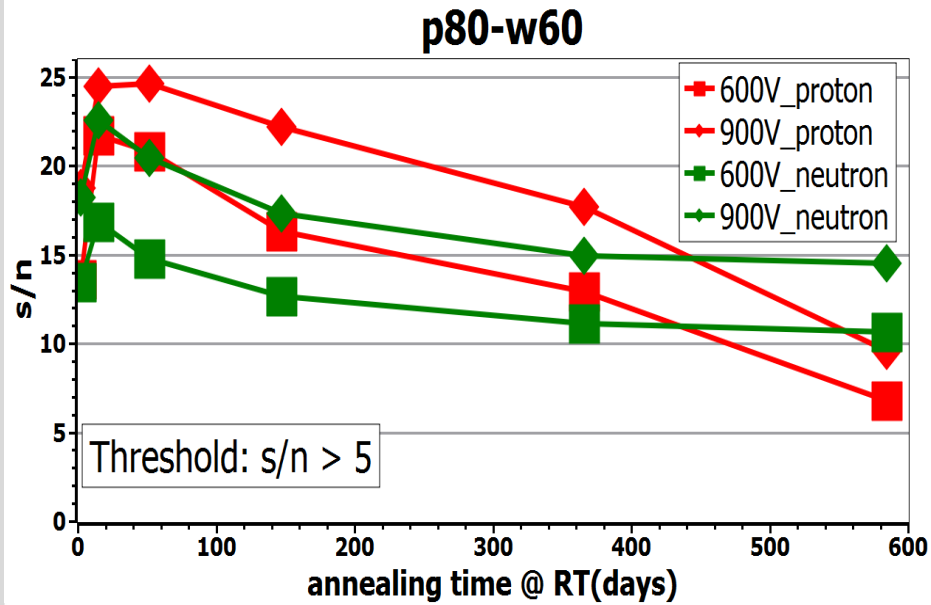
Thank you for your attention.

BACKUP

CCE @ $F = 1 \cdot 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$

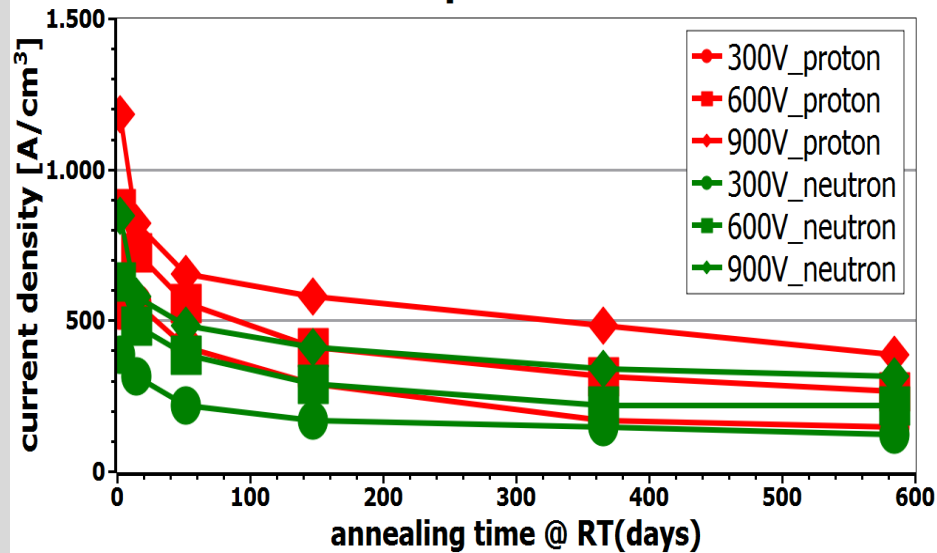


$s/n @ F = 1 \cdot 10^{15} n_{eq}/cm^2$

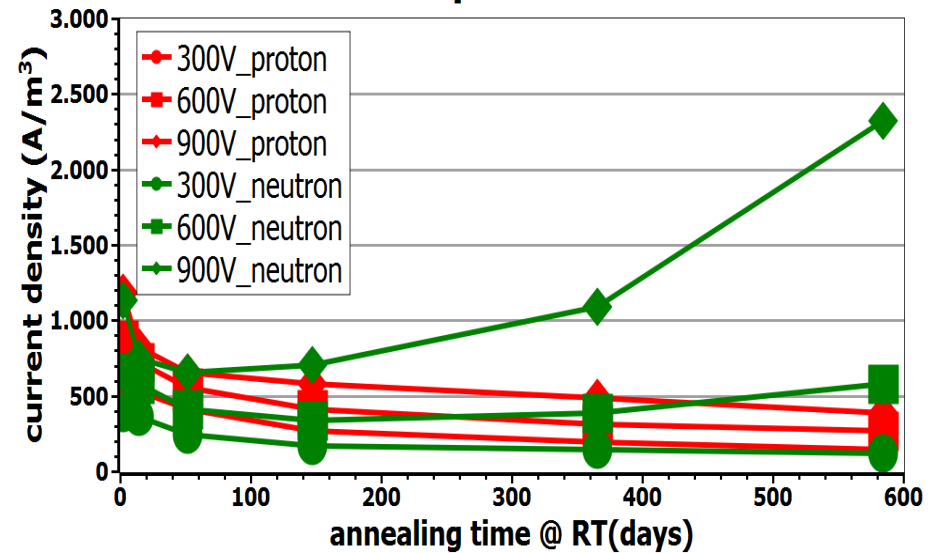


Leakage current @ $F = 1 \cdot 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2$

p80-w60

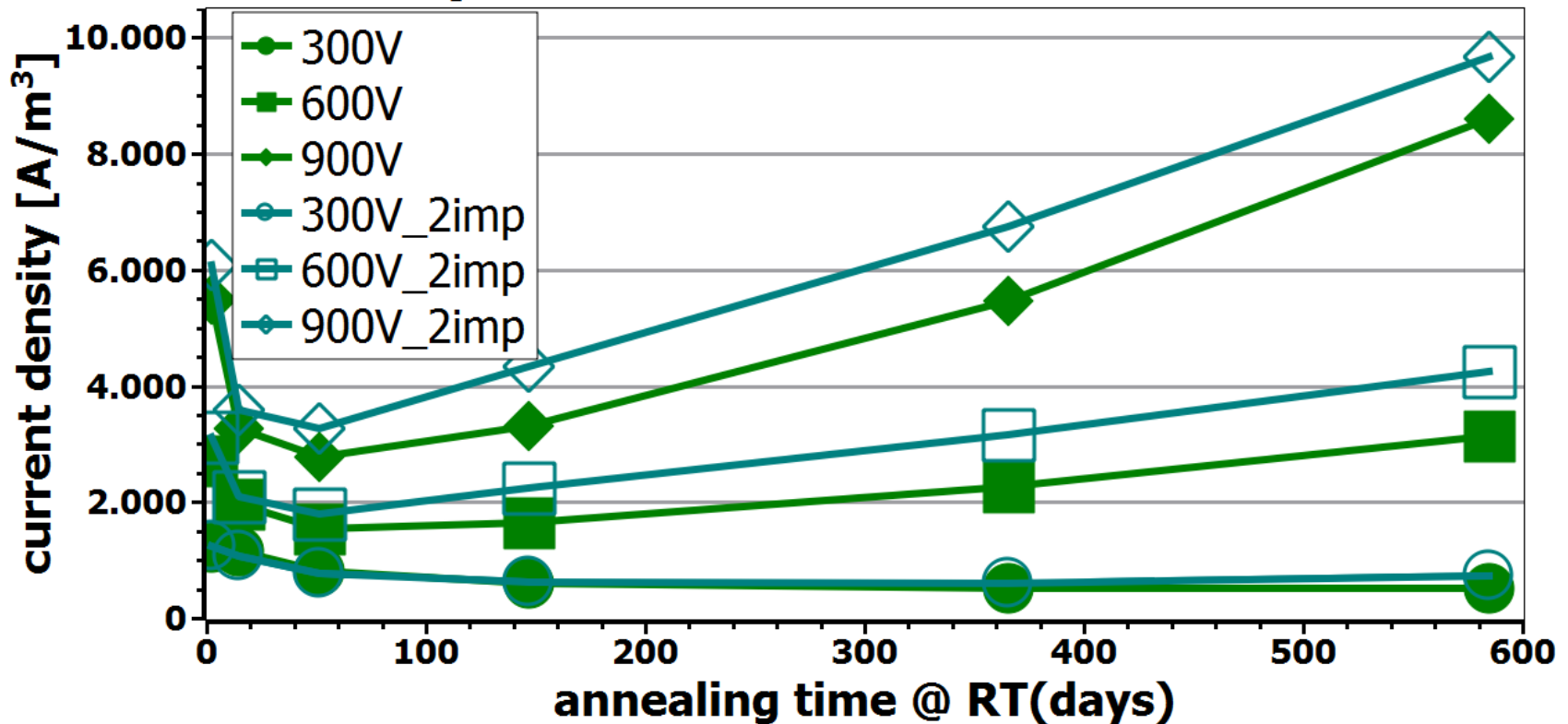


p80-w6



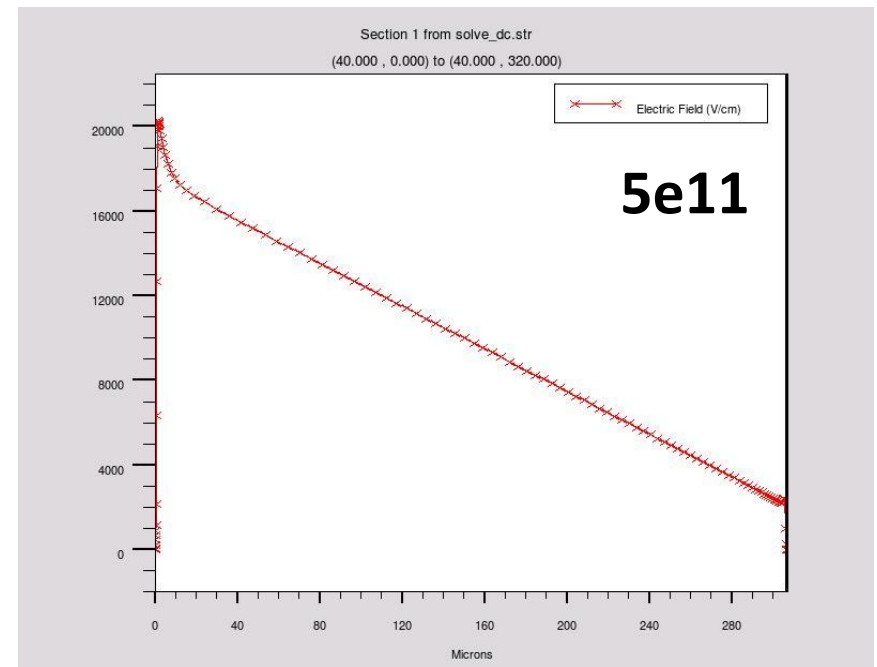
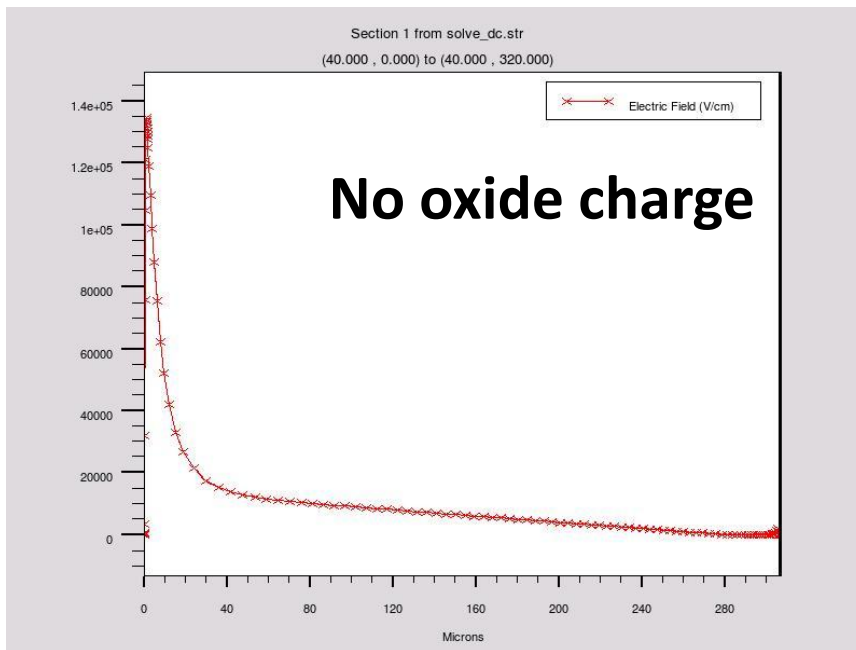
Comparison of implantation energy (Leakage current)

p80-w6: neutron irradiation



- Increase in noise can be explained by current
- Higher current seen for high voltages at the 2imp-sensor

Oxide Charge



Possible explanation for difference between protons and neutrons

- Proton irradiation generates positive charge in the oxide / interface between silicon and oxide
- Neutron irradiation doesn't create much oxide / interface charge
- Preliminary simulation with interface charge shows:
 - Electric field decreases at the strip with increasing interface charge

